제원조서

품명	식각장비	수량	1
		설치장소	3호관
		담당교수	

제원 또는 규격	비고
1. Model : CIONE6-RF-1MP RF Plasma Processing System - Dual mode process chamber, 1 x gas channel with 200sccm MFC, 300W RF generator 2. Additional gas channel - MFC(Mass Flow Controller), Gas line package, S/W - Model changed to CIONE6-RF-4MP (O2, Ar, CF4, CHF3) 3. Vacuum Pump Set - Oil Rotary Pump (Model RV 12 from Edwards) - 1.5m-long S/S Flexible Pipe, Oil Mist Filter, NW25 Flange, Selas & Clamp 4. Recirculation Chiller for Cooling Electrode - Max. 13 liter/min, 1.4kW cooling capacity, +/- 0.3 ℃ accuracy 5. Dry Scrubber - 10L 6. Process gas cylinder - 10L + Regulator (O2, Ar, CF4, CHF3)	

부서장	전기전자통신공학부		